

## **LISTING OF THE CLAIMS**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**1. (Canceled)**

**2. - 3. (Previously Canceled)**

**4. - 10. (Canceled)**

**11. (Previously Canceled)**

**12. - 14. (Canceled)**

**15. - 16. (Previously Canceled)**

**17. - 21. (Canceled)**

**22. (New)** A substrate processing apparatus for performing resist coating processing and development processing on a substrate, comprising:

a) a coating unit provided with a first plurality of processing parts including a coating part for performing resist coating processing on a substrate;

b) a development unit provided with a second plurality of processing parts including a development part for performing development processing on a substrate;

c) an inspection unit provided with a plurality of inspection parts for performing substrate inspection of different contents respectively, said inspection unit being arranged between said coating unit and said development unit;

d) a transport part for transporting a substrate to said first plurality of processing parts, said second plurality of processing parts and said plurality of inspection parts; and

e) a transportation control part for controlling said transport part so that each of part or all of a set of plural substrates subjected to the same processing is transported to a single inspection part selected from said plurality of inspection parts, thereby transporting at least one and less than all of said set of plural substrates to each of said plurality of inspection parts.

**23. (New)** The substrate processing apparatus according to claim 22, further comprising:  
f) an indexer for introducing unprocessed substrates and receiving processed substrates,  
wherein said transportation control part controls said transport part so that a substrate introduced from said indexer into said coating unit and coated with resist is passed through said development unit and is transported outside said substrate processing apparatus, and also that a substrate exposed outside said substrate processing apparatus and thereafter returned to said development unit and developed is passed through said coating unit and is transported to said indexer.

**24. (New)** The substrate processing apparatus according to claim 23, wherein said transport part includes:

a first transport robot provided in said coating unit for transporting a substrate to said first plurality of processing parts; and

a second transport robot provided in said development unit for transporting a substrate to said second plurality of processing parts,

wherein both said first transport robot and said second transport robot are capable of transporting a substrate to said inspection unit.

**25. (New)** The substrate processing apparatus according to claim 24, wherein a processing condition in any processing part of said first and second plurality of processing parts is changed on the basis of inspection results obtained by said plurality of inspection parts.

**26. (New)** The substrate processing apparatus according to claim 25, wherein said plurality of inspection parts include at least two of a resist film thickness measuring part, a pattern line width measuring part, a pattern overlay measuring part and a macro defect inspection part.

**27. (New)** A substrate processing apparatus for performing resist coating processing and development processing on a substrate, comprising:

a) a coating unit provided with a first plurality of processing parts including a coating part for performing resist coating processing on a substrate;

b) a development unit provided with a second plurality of processing parts including a development part for performing development processing on a substrate;

c) an inspection unit provided with an inspection part capable of performing substrate inspection of a plurality of contents, said inspection unit being arranged between said coating unit and said development unit;

d) a transport part for transporting a substrate to said first plurality of processing parts, said second plurality of processing parts and said inspection part; and

e) a transportation control part for controlling said transport part so that each of part or all of a set of plural substrates subjected to the same processing is transported to said inspection part,

wherein a substrate transported to said inspection part undergoes substrate inspection of a single content selected from said plurality of contents that said inspection part is capable of performing, so that said inspection part performs substrate inspection of each of said plurality of contents on at least one and less than all of said set of plural substrates.

**28. (New)** The substrate processing apparatus according to claim 27, further comprising:

f) an indexer for introducing unprocessed substrates and receiving processed substrates,

wherein said transportation control part controls said transport part so that a substrate introduced from said indexer into said coating unit and coated with resist is passed through said development unit and is transported outside said substrate processing apparatus, and also that a substrate exposed outside said substrate processing apparatus and thereafter returned to said development unit and developed is passed through said coating unit and is transported to said indexer.

**29. (New)** The substrate processing apparatus according to claim 28, wherein said plurality of contents that said inspection part is capable of performing comprises resist film thickness measurement, pattern line width measurement and pattern overlay measurement.

**30. (New)** A substrate processing system for performing resist coating processing and development processing on a substrate, comprising:

a) a coating unit provided with a first plurality of processing parts including a coating part for performing resist coating processing on a substrate;

b) a development unit provided with a second plurality of processing parts including a development part for performing development processing on a substrate;

c) an inspection unit provided with a plurality of inspection parts for performing substrate inspection of different contents respectively, said inspection unit being arranged between said coating unit and said development unit;

d) a transport part for transporting a substrate to said first plurality of processing parts, said second plurality of processing parts and said plurality of inspection parts;

e) an indexer provided to be connected to said coating unit for introducing unprocessed substrates and receiving processed substrates;

f) an exposure unit provided to be connected to said development unit for performing exposure processing to a substrate coated with resist; and

g) a transportation control part for controlling said transport part so that each of part or all of a set of plural substrates subjected to the same processing is transported to a single inspection part selected from said plurality of inspection parts, thereby transporting at least one and less than all of said set of plural substrates to each of said plurality of inspection parts.

**31. (New)** The substrate processing system according to claim 30, wherein said plurality of inspection parts include at least two of a resist film thickness measuring part, a pattern line width measuring part, a pattern overlay measuring part and a macro defect inspection part.

**32. (New)** A substrate processing system for performing resist coating processing and development processing on a substrate, comprising:

a) a coating unit provided with a first plurality of processing parts including a coating part for performing resist coating processing on a substrate;

b) a development unit provided with a second plurality of processing parts including a development part for performing development processing on a substrate;

c) an inspection unit provided with an inspection part capable of performing substrate inspection of a plurality of contents, said inspection unit being arranged between said coating unit and said development unit;

d) a transport part for transporting a substrate to said first plurality of processing parts, said second plurality of processing parts and said inspection part;

e) an indexer provided to be connected to said coating unit for introducing unprocessed substrates and receiving processed substrates;

f) an exposure unit provided to be connected to said development unit for performing exposure processing to a substrate coated with resist; and

g) a transportation control part for controlling said transport part so that each of parts or all of a set of plural substrates subjected to the same processing is transported to said inspection part,

wherein a substrate transported to said inspection part undergoes substrate inspection of a single content selected from said plurality of contents that said inspection part is capable of performing, so that said inspection part performs substrate inspection of each of said plurality of contents on at least one and less than all of said set of plural substrates.

**33. (New)** The substrate processing system according to claim 32, wherein said plurality of contents that said inspection part is capable of performing comprises resist film thickness measurement, pattern line width measurement and pattern overlay measurement.